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LIST OF	REFE	RENCES CITED BY API	PLICANT	Akira HOKAZONO, et al.				
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U.S. PATENT DOCUMENTS								
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OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)								
A.S.W. WONG, et al., "Enhanced Thermal Stability of NiSi Films on 20KEV BF ₂ + Implanted (100) Si", SYMPOSIUM B								
MI	AW	SILICON MATERIAL-P 2002, 1 Page	PROCESSING	G CHARACTERIZATION AND RELIABILIT	ITY, MRS 2	2002 Spring	ng Meeting, April 1-5,	
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